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INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

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- (54) Title: **HIGH PURITY TANTALUM AND PRODUCTS CONTAINING THE SAME LIKE SPUTTER TARGETS**
 (54) Titre: **TANTALE DE GRANDE PURETE ET PRODUITS LE CONTENANT, TELS QUE LES CIBLES PULVERISEES**

(57) Abstract

High purity tantalum metals and alloys containing the same are described. The tantalum metal preferably has a purity of at least 99.995 % and more preferably at least 99.999 %. In addition, tantalum metal and alloys thereof are described, which either have a grain size of about 50 microns or less, or a texture in which a (100) intensity within any 5 % increment of thickness is less than about 15 random, or an incremental log ratio of (111):(100) intensity of greater than about -4.0, or any combination of these properties. Also described are articles and components made from the tantalum metal which include, but are not limited to, sputtering targets, capacitor cans, resistive film layers, wire, and the like. Also disclosed is a process for making the high purity metal which includes the step of reacting a salt-containing tantalum with at least one compound capable of reducing this salt to tantalum powder and a second salt in a reaction container. The reaction container or liner in the reaction container and the agitator or liner on the agitator are made from a metal material having the same of higher vapor pressure of melted tantalum. The high purity tantalum preferably has a fine and uniform microstructure.

(57) Abrégé

La présente invention concerne des métaux de tantale de grande pureté et des alliages renfermant ce dernier. De préférence, le métal de tantale présente une pureté d'au moins 99,995 % et plus préféablement au moins 99,999 %. En outre, cette invention concerne le métal de tantale et ses alliages, qui soit présentent une grosseur de grain d'environ 50 microns ou moins, soit une texture dans laquelle une intensité (100) se situant dans n'importe quel 5 % d'augmentation d'épaisseur est inférieure à environ 15 d'aléatoire, ou un rapport logarithmique d'augmentation d'intensité (111):(100) supérieur à environ 4,0, ou n'importe quelle combinaison de ces propriétés. Par ailleurs, cette invention concerne des articles et des composants à base de tantale, notamment des cibles pulvérisées, des boîtiers de condensateurs, des couches pelliculaires résistives, des câbles, et autres. De plus, cette invention concerne un processus de fabrication de ce métal de grande pureté consistant à faire réagir un tantale contenant du sel avec au moins un composé capable de réduire ce sel en poudre de tantale, et un second sel dans un récipient de réaction. Ce récipient de réaction, ou le revêtement intérieur du récipient à réaction, et l'agitateur, ou le revêtement interne de l'agitateur, sont fabriqués avec un matériau métallique caractérisé par une pression de vapeur supérieure à celle du tantale fondu. De préférence, le tantale de grande pureté possède une microstructure fine et uniforme.

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(54) Title: **HIGH PURITY TANTALUM AND PRODUCTS CONTAINING THE SAME LIKE SPUTTER TARGETS**

(57) Abstract

High purity tantalum metals and alloys containing the same are described. The tantalum metal preferably has a purity of at least 99.995 % and more preferably at least 99.999 %. In addition, tantalum metal and alloys thereof are described, which either have a grain size of about 50 microns or less, or a texture in which a (100) intensity within any 5 % increment of thickness is less than about 15 random, or an incremental log ratio of (111):(100) intensity of greater than about -4.0, or any combination of these properties. Also described are articles and components made from the tantalum metal which include, but are not limited to, sputtering targets, capacitor cans, resistive film layers, wire, and the like. Also disclosed is a process for making the high purity metal which includes the step of reacting a salt-containing tantalum with at least one compound capable of reducing this salt to tantalum powder and a second salt in a reaction container. The reaction container or liner in the reaction container and the agitator or liner on the agitator are made from a metal material having the same or higher vapor pressure of melted tantalum. The high purity tantalum preferably has a fine and uniform microstructure.

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Description

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HIGH PURITY TANTALUM AND PRODUCTS CONTAINING THE SAME LIKE SPUTTER TARGETS

BACKGROUND OF THE INVENTION

The present invention relates to metals, in particular tantalum, and products made from tantalum as well as methods of making and processing the tantalum.

In industry, there has always been a desire to form higher purity metals for a variety of reasons. With respect to tantalum, higher purity metals are especially desirable due to tantalum's use as a sputtering target and its use in electrical components such as capacitors. Thus, impurities in the metal can have an undesirable effect on the properties of the articles formed from the tantalum.

When tantalum is processed, the tantalum is obtained from ore and subsequently crushed and the tantalum separated from the crushed ore through the use of an acid solution and density separation of the acid solution containing the tantalum from the acid solution containing niobium and other impurities. The acid solution containing the tantalum is then crystallized into a salt and this tantalum containing salt is then reacted with pure sodium in a vessel having an agitator typically constructed of nickel alloy material, wherein tungsten or molybdenum is part of the nickel alloy. The vessel will typically be a double walled vessel with pure nickel in the interior surface. The salt is then dissolved in water to obtain tantalum powder. However, during such processing, the tantalum powder is contaminated by the various surfaces that it comes in contact with such as the tungsten and/or molybdenum containing surfaces. Many contaminants can be volatilized during subsequent melting, except highly soluble refractory metals (e.g., Nb, Mo, and W). These impurities can be quite difficult or impossible to remove, thus preventing a very high purity tantalum product.

Accordingly, there is a desire to obtain higher purity tantalum products which substantially avoid the contaminations obtained during the processing discussed above. Also, there is a desire to have a tantalum product having higher purity, a fine grain size, and/or a uniform texture. Qualities such as fine grain size can be an important property for sputtering targets made from tantalum since fine grain size can lead to improved uniformity of thickness of the sputtered deposited film. Further,

5 other products containing the tantalum having fine grain size can lead to improved homogeneity of
deformation and enhancement of deep drawability and stretchability which are beneficial in making
10 capacitors cans, laboratory crucibles, and increasing the lethality of explosively formed penetrators
(EFP's). Uniform texture in tantalum containing products can increase sputtering efficiency (e.g.,
5 greater sputter rate) and can increase normal anisotropy (e.g., increased deep drawability), in perform
15 products.

SUMMARY OF THE PRESENT INVENTION

20 A feature of the present invention is to provide a high purity tantalum product exhibiting a fine
10 grain structure and/or uniform texture.

25 Another feature of the present invention is to provide articles, products, and/or components
containing the high purity tantalum.

30 An additional feature of the present invention is to provide processes to make the high purity
15 tantalum product as well as the articles, products, and/or components containing the high purity
tantalum.

35 Additional features and advantages of the present invention will be set forth in part in the
description which follows, and in part will be apparent from the description, or may be learned by
practice of the present invention. The objectives and other advantages of the present invention will be
realized and attained by means of the elements and combinations particularly pointed out in the
40 20 description and appended claims.

45 To achieve these and other advantages, and in accordance with the purpose of the present
invention, as embodied and broadly described herein, the present invention relates to tantalum metal
having a purity of at least 99.995% and more preferably at least 99.999%. The tantalum metal
preferably has a fine grain structure and/or uniform texture.

50 25 The present invention further relates to an alloy or mixture comprising tantalum, wherein the
tantalum present in the alloy or mixture has a purity of at least 99.995% and more preferably at least

5 99.999%. The alloy or mixture (e.g., at least the tantalum present in the alloy or mixture) also preferably has a fine grain structure and/or uniform texture.

10 The present invention also relates to a high purity tantalum, e.g., suitable for use as a sputtering target, having a fully recrystallized grain size with an average grain size of about 150 μm or less and/or having a primary (111)-type texture substantially throughout the thickness of the tantalum and preferably throughout the entire thickness of the tantalum metal and/or having an absence of strong (100) texture bands within the thickness of the tantalum.

15 The present invention further relates to manufacturing plate and sheet from the above-mentioned tantalum by flat-forging the tantalum, machining into rolling slabs, annealing rolling slabs, 20 rolling into plate or sheet, then annealing the plate or sheet. Final products such as sputtering targets can be then machined from the annealed plate or sheet.

25 The present invention also relates to a sputtering target comprising the above-described tantalum and/or alloy. The sputtering target can also be formed by radial forging and subsequent round processing to produce billets or slugs, which are then forged and rolled to yield discs, which can 30 then be machined and annealed.

35 The present invention further relates to resistive films and capacitors comprising the above-described tantalum and/or alloy.

The present invention also relates to articles, components, or products which comprise at least in part the above-described tantalum and/or alloy.

40 20 Also, the present invention relates to a process of making the above-described tantalum which involves reacting a salt-containing tantalum with pure sodium or other suitable salt in a reactive container or pot and an agitator which both are made from or have a liner comprising a metal or alloy thereof which has the same or higher vapor pressure as tantalum at the melting point of tantalum.

45 The present invention further relates to processing tantalum powder by melting the tantalum 25 powder in a high vacuum of 10^{-2} torr or more. The pressure above the melt is lower than the vapor pressures of the impurities existing in the tantalum. Preferably, the melting of the tantalum powder is 50

5 accomplished by electron beam melting.

10 It is to be understood that both the foregoing general description and the following detailed description are exemplary and explanatory only and are intended to provide further explanation of the present invention, as claimed.

15 **BRIEF DESCRIPTION OF THE DRAWINGS**

20 Figures 1(A-B)-11(A-B) are graphs and corresponding data relating to texture gradient (incremental thickness vs. random) and log ratio (111):(100) gradients (incremental thickness vs. Ln (111/100)) of high purity tantalum plates of the present invention.

10 **DETAILED DESCRIPTION OF THE PRESENT INVENTION**

25 The present invention relates to a tantalum metal having a purity of at least 99.995%. Preferably, the tantalum metal has a purity of at least 99.999% and can range in purity from about 99.995% to about 99.999% or more. Other ranges include about 99.998% to about 99.999% and from
30 about 99.999% to about 99.9992% and from about 99.999% to about 99.9995%. The present invention further relates to a metal alloy which comprises the high purity tantalum metal, such as a tantalum based alloy or other alloy which contains the high purity tantalum as one of the components
35 of the alloy.

40 The impurities that may be present in the high purity tantalum metal are less than or equal to .005% and typically comprise other body-centered cubic (bcc) refractory metals of infinite solubility in tantalum, such as niobium, molybdenum, and tungsten.

45 The tantalum metal and alloys thereof containing the tantalum metal preferably have a texture which is advantageous for particular end uses, such as sputtering. In other words, when the tantalum metal or alloy thereof is formed into a sputtering target having a surface and then sputtered, the texture
25 of the tantalum metal in the present invention leads to a sputtering target which is easily sputtered and, very few if any areas in the sputtering target resist sputtering. Further, with the texture of the tantalum
50

5 metal of the present invention, the sputtering of the sputtering target leads to a very uniform sputtering
erosion thus leading to a sputtered film which is therefore uniform as well. It is preferred that the
10 tantalum having any purity, but preferably a purity of at least about 99.995%, has a grain size of about
150 microns or less. Preferably, the tantalum metal is at least partially recrystallized, and more
5 preferably at least about 80% of the tantalum metal is recrystallized and even more preferably at least
about 98% of the tantalum metal is recrystallized. Most preferably, the tantalum metal is fully
15 recrystallized.

Also, it is preferred that the tantalum metal have a fine texture. More preferably the texture is
20 such that the (100) peak intensity within any 5% incremental thickness of the tantalum is less than
about 15 random, and/or has a natural log (Ln) ratio of (111):(100) center peak intensities within the
same increment greater than about -4.0 (i.e., meaning, -4.0, -3.0, -2.0, -1.5, -1.0 and so on) or has both
25 the (100) centroid intensity and the ratio. The center peak intensity is preferably from about 0 random
to about 10 random, and more preferably is from about 0 random to about 5 random. Other (100)
centroid intensity ranges include, but are not limited to, from about 1 random to about 10 random and
30 from about 1 random to about 5 random. Further, the log ratio of (111):(100) center peak intensities is
from about -4.0 to about 15 and more preferably from about -1.5 to about 7.0. Other suitable ranges
35 of log ratios include, but are not limited to, about -4.0 to about 10, and from about -3.0 to about 5.0.
Most preferably, the tantalum metal has the desired purity of at least about 99.995% and the preferred
grain size and preferred texture with regard to the (100) incremental intensity and the (111):(100) ratio
40 of incremental centroid intensities. The method and equipment that can be used to characterize the
texture are described in Adams et al., Materials Science Forum, Vol. 157-162 (1994), pp. 31-42;
Adams et al., Metallurgical Transactions A, Vol. 24A, April 1993-No. 4, pp. 819-831; Wright et al.,
45 International Academic Publishers, 137 Chaonei Dajie, Beijing, 1996 ("Textures of Material:
Proceedings of the Eleventh International Conference on Textures of Materials); Wright, Journal of
25 Computer-Assisted Microscopy, Vol. 5, No. 3 (1993), all incorporated in their entirety by reference
50 herein.

5 The high purity tantalum metal of the present invention can be used in a number of areas. For
instance, the high purity tantalum metal can be made into a sputtering target or into chemical energy
10 (CE) munitions warhead liner which comprises the high purity metal. The high purity metal can also
be used and formed into a capacitor anode or into a resistive film layer. The tantalum metal of the
5 present invention can be used in any article or component which conventional tantalum is used and the
methods and means of making the various articles or components containing the conventional tantalum
15 can be used equally here in incorporating the high purity tantalum metal into the various articles or
components. For instance, the subsequent processing used in making sputtering targets, such as the
20 backing plate, described in U.S. Patent Nos. 5,753,090, 5,687,600, and 5,522,535 can be used here and
10 these patents are incorporated in their entirety by reference herein.

 Generally, a process that can be used to make the high purity tantalum metal of the present
25 invention involves a refining process, a vacuum melting process, and a thermal mechanical process. In
this process or operation, the refining process involves the steps of extracting tantalum metal
preferably in the form a powder from ore containing tantalum and preferably the ore-containing
30 tantalum selected has low amounts of impurities, especially, low amounts of niobium, molybdenum,
and tungsten. More preferably, the amount of niobium, molybdenum, and tungsten is below about 10
35 ppm, and most preferably is below about 8 ppm. Such a selection leads to a purer tantalum metal.
After the refining process, the vacuum melting process is used to purge low melting point impurities,
such as alkyls and transition metals from the tantalum while consolidating the tantalum material into a
40 20 fully dense, malleable ingot. Then, after this process, a thermal mechanical process can be used which
can involve a combination of cold working and annealing of a tantalum which further ensures that the
preferred grain size and/or preferred texture and uniformity are achieved, if desired.

45 The high purity tantalum metal preferably may be made by reacting a salt-containing tantalum
with at least one agent (e.g., compound or element) capable of reducing this salt to the tantalum metal
25 and further results in the formation of a second salt in a reaction container. The reaction container can
50 be any container typically used for the reaction of metals and should withstand high temperatures on

5 the order of about 800°C to about 1,200°C. For purposes of the present invention, the reaction
container or the liner in the reaction container, which comes in contact with the salt-containing
10 tantalum and the agent capable of reducing the salt to tantalum, is made from a material having the
same or higher vapor pressure as tantalum at the melting point of the tantalum. The agitator in the
5 reaction container can be made of the same material or can be lined as well. The liner can exist only in
the portions of the reaction container and agitator that come in contact with the salt and tantalum.
15 Examples of such metal materials which can form the liner or reaction container include, but are not
limited to, metal-based materials made from nickel, chromium, iron, manganese, titanium, zirconium,
20 hafnium, vanadium, ruthenium, cobalt, rhodium, palladium, platinum, or any combination thereof or
10 alloy thereof as long as the alloy material has the same or higher vapor pressure as the melting point of
tantalum metal. Preferably, the metal is a nickel or a nickel-based alloy, a chromium or a chromium-
25 based alloy, or an iron or an iron-based alloy. The liner, on the reaction container and/or agitator, if
present, typically will have a thickness of from about .5 cm to about 3 cm. Other thicknesses can be
used. It is within the bounds of the present invention to have multiple layers of liners made of the same
30 or different metal materials described above.
15

The salt-containing tantalum can be any salt capable of having tantalum contained therein
such as a potassium-fluoride tantalum. With respect to the agent capable of reducing the salt to
35 tantalum and a second salt in the reaction container, the agent which is capable of doing this reduction
is any agent which has the ability to result in reducing the salt-containing tantalum to just tantalum
40 20 metal and other ingredients (e.g. salt(s)) which can be separated from the tantalum metal, for example,
by dissolving the salts with water or other aqueous sources. Preferably, this agent is sodium. Other
examples include, but are not limited to, lithium, magnesium, calcium, potassium, carbon, carbon
45 monoxide, ionic hydrogen, and the like. Typically, the second salt which also is formed during the
reduction of the salt-containing tantalum is sodium fluoride. Details of the reduction process which
25 can be applied to the present invention in view of the present application are set forth in Kirk-Othmer,
50 Encyclopedia of Chemical Technology, 3rd Edition, Vol. 22, pp. 541-564, U.S. Patent Nos. 2,950,185;

5 3,829,310; 4,149,876; and 3,767,456. Further details of the processing of tantalum can be found in
10 U.S. Patent Nos. 5,234,491; 5,242,481; and 4,684,399. All of these patents and publications are
incorporated in their entirety by reference herein.

15 The above-described process can be included in a multi-step process which can begin with
5 low purity tantalum, such as ore-containing tantalum. One of the impurities that can be substantially
15 present with the tantalum is niobium. Other impurities at this stage are tungsten, silicon, calcium, iron,
manganese, etc. In more detail, low purity tantalum can be purified by mixing the low purity tantalum
which has tantalum and impurities with an acid solution. The low purity tantalum, if present as an ore,
20 should first be crushed before being combined with an acid solution. The acid solution should be
10 capable of dissolving substantially all of the tantalum and impurities, especially when the mixing is
occurring at high temperatures.

25 Once the acid solution has had sufficient time to dissolve substantially, if not all, of the solids
containing the tantalum and impurities, a liquid solid separation can occur which will generally
remove any of the undissolved impurities. The solution is further purified by liquid-liquid extraction.
30 15 Methyl isobutyl ketone (MIBK) can be used to contact the tantalum rich solution, and deionized water
can be added to create a tantalum fraction. At this point, the amount of niobium present in the liquid
containing tantalum is generally below about 25 ppm.

35 Then, with the liquid containing at least tantalum, the liquid is permitted to crystallize into a
salt with the use of vats. Typically, this salt will be a potassium tantalum fluoride salt. More
40 20 preferably, this salt is K_2TaF_7 . This salt is then reacted with an agent capable of reducing the salt into
1) tantalum and 2) a second salt as described above. This compound will typically be pure sodium and
the reaction will occur in a reaction container described above. As stated above, the second salt
45 byproducts can be separated from the tantalum by dissolving the salt in an aqueous source and
washing away the dissolved salt. At this stage, the purity of the tantalum is typically 99.50 to 99.99%

50 25 Ta.


5 Once the tantalum powder is extracted from this reaction, any impurities remaining, including
any contamination from the reaction container, can be removed through melting of the tantalum
10 powder.

15 The tantalum powder can be melted a number of ways such as a vacuum arc remelt or an
electron beam melting. Generally, the vacuum during the melt will be sufficient to remove
substantially any existing impurities from the recovered tantalum so as to obtain high purity tantalum.
20 Preferably, the melting occurs in a high vacuum such as 10^{-4} torr or more. Preferably, the pressure
above the melted tantalum is lower than the vapor pressures of the metal impurities in order for these
impurities, such as nickel and iron to be vaporized. The diameter of the cast ingot should be as large
25 as possible, preferably greater than 9 1/4 inches. The large diameter assures a greater melt surface to
vacuum interface which enhances purification rates. In addition, the large ingot diameter allows for a
greater amount of cold work to be imparted to the metal during processing, which improves the
attributes of the final products. Once the mass of melted tantalum consolidates, the ingot formed will
30 have a purity of 99.995% or higher and preferably 99.999% or higher. The electron beam processing
preferably occurs at a melt rate of from about 300 to about 800 lbs. per hour using 20,000 to 28,000
volts and 15 to 40 amps, and under a vacuum of from about 1×10^{-3} to about 1×10^{-6} Torr. More
35 preferably, the melt rate is from about 400 to about 600 lbs. per hour using from 24,000 to 26,000 volts
and 17 to 36 amps, and under a vacuum of from about 1×10^{-4} to 1×10^{-5} Torr. With respect to the
VAR processing, the melt rate is preferably of 500 to 2,000 lbs. per hour using 25-45 volts and 12,000
40 to 22,000 amps under a vacuum of 2×10^{-2} to 1×10^{-4} Torr, and more preferably 800 to 1200 lbs. per
hour at from 30 to 60 volts and 16,000 to 18,000 amps, and under a vacuum of from 2×10^{-2} to $1 \times$
45 10^{-4} Torr.

50 The high purity tantalum ingot can then be thermomechanically processed to produce the high
purity tantalum containing product. The fine, and preferably fully recrystallized, grain structure and/or
25 uniform texture is imparted to the product through a combination of cold and/or warm working and in-
process annealing. The high purity tantalum product preferably exhibits a uniform texture of mixed or
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5 primary (111) throughout its thickness as measured by orientation imaging microscopy (OIM) or other
acceptable means. With respect to thermomechanical processing, the ingot can be subjected to rolling
10 and/or forging processes and a fine, uniform microstructure having high purity can be obtained. The
high purity tantalum has an excellent fine grain size and/or a uniform distribution. The high purity
5 tantalum preferably has an average recrystallized grain size of about 150 microns or less, more
preferably about 100 microns or less, and even more preferably about 50 microns or less. Ranges of
15 suitable average grain sizes include from about 25 to about 150 microns; from about 30 to about 125
microns, and from about 30 to about 100 microns.

20 The resulting high purity metal of the present invention, preferably has 10 ppm or less metallic
10 impurities and preferably 50 ppm or less O₂, 25 ppm or less N₂, and 25 ppm or less carbon. If a purity
level of about 99.995 is desired, then the resulting high purity metal preferably has metallic impurities
25 of about 50 ppm or less, and preferably 50 ppm or less O₂, 25 ppm or less N₂, and 25 ppm or less
carbon.

30  With respect to taking this ingot and forming a sputtering target, the following process can be
15 used. In one embodiment, the sputtering target made from the high purity tantalum metal can be made
by mechanically or chemically cleaning the surfaces of the tantalum metal, wherein the tantalum metal
has a sufficient starting cross-sectional area to permit the subsequent processing steps described
35 below. Preferably the tantalum metal has a cross-sectional area of at least 9 1/4 inches or more. The
next step involves flat forging the tantalum metal into one or more rolling slabs. The rolling slab(s)
40 20 has a sufficient deformation to achieve substantially uniform recrystallization after the annealing step
immediately following this step as described below. The rolling slab(s) is then annealed in vacuum
and at a sufficient temperature to achieve at least partial recrystallization of the rolling slab(s).
45 Preferred annealing temperatures and times are set forth below and in the examples. The rolling slab(s)
is then subjected to cold or warm rolling in both the perpendicular and parallel directions to the axis of
25 the starting tantalum metal (e.g., the tantalum ingot) to form at least one plate. The plate is then
50 subjected to flattening (e.g., level rolling). The plate is then annealed a final time at a sufficient
55

5 temperature and for a sufficient time to have an average grain size of equal to or less than about 150
10 microns and a texture substantially void of (100) textural bands. Preferably, no (100) textural bands
exist. The plate can then be mechanically or chemically cleaned again and formed into the sputtering
15 target having any desired dimension. Typically, the flat forging will occur after the tantalum metal is
placed in air for at least about 4 hours at temperatures ranging from ambient to about 370°C. Also,
20 preferably before cold rolling, the rolling slabs are annealed at a temperature (e.g., from about 950°C
to about 1500°C) and for a time (e.g., from about ½ hour to about 8 hours) to achieve at least partial
recrystallization of the tantalum metal. Preferably the cold rolling is transverse rolling at ambient
temperatures and the warm rolling is at temperatures of less than about 370°C.

10 With respect to annealing of the tantalum plate, preferably this annealing is in a vacuum
annealing at a temperature and for a time sufficient to achieve complete recrystallization of the
25 tantalum metal. The examples in this application set forth further preferred details with respect to this
processing.

30 Another way to process the tantalum metal into sputtering targets involves mechanically or
15 chemically clean surfaces of the tantalum metal (e.g., the tantalum ingot), wherein the tantalum metal
has a sufficient starting cross-sectional area to permit the subsequent processing as described above.
35 The next step involves round forging the tantalum metal into at least one rod, wherein the rod has
sufficient deformation to achieve substantially uniform recrystallization either after the annealing step
which occurs immediately after this step or the annealing step prior to cold rolling. The tantalum rod
40 is then cut into billets and the surfaces mechanically or chemically cleaned. An optional annealing
step can occur afterwards to achieve at least partial recrystallization. The billets are then axially
45 forged into performs. Again, an optional annealing step can occur afterwards to achieve at least partial
recrystallization. However, at least one of the optional annealing steps or both are done. The performs
are then subjected to cold rolling into at least one plate. Afterwards, the surfaces of the plate(s) can be
25 optionally mechanically or chemically clean. Then, the final annealing step occurs to result in an
50 average grain size of about 150 microns or less and a texture substantially void of (100) textural bands,

5 if not totally void of (100) textural bands. The round forging typically occurs after subjecting the
tantalum metal to temperatures of about 370°C or lower. Higher temperatures can be used which
10 results in increased oxidation of the surface. Preferably, prior to forging the billets, the billets are
annealed. Also, the performs, prior to cold rolling can be annealed. Typically, these annealing
5 temperatures will be from about 900°C to about 1200°C. Also, any annealing is preferably vacuum
15 annealing at a sufficient temperature and for a sufficient time to achieve recrystallization of the
tantalum metal.

20 Preferably, the sputtering targets made from the high purity tantalum have the following
dimensions: a thickness of from about 0.080 to about 1.50", and a surface area from about 7.0 to about
10 1225 square inches.

25 The high purity tantalum preferably has a primary or mixed (111) texture, and a minimum
(100) texture throughout the thickness of the sputtering target, and is sufficiently void of (100) textural
bands.

30 The tantalum metal of the present invention can be used in any application or product that
15 uses conventional tantalum metal as a component or as part of a component. For instance, the
tantalum metal can be a component or part of a component in integrated circuits, such as
35 semiconductors and the like. The designs described in U.S. Patent Nos.: 5,987,635; 5,987,560;
5,986,961; 5,986,960; 5,986,940; 5,986,496; 5,986,469; 5,986,410; 5,986,320; 5,986,299; 5,986,294;
5,985,697; and 5,982,218 can be used as well as other conventional designs and each of these patents
40 20 are incorporated herein in their entireties by reference. The tantalum metal can be present in any
device which typically uses sputtering techniques to deposit metal to form a component or part of a
component on a device.

45 The present invention will be further clarified by the following examples, which are intended
to be purely exemplary of the present invention.

50

55

EXAMPLES

Example 1

Numerous sublots of sodium-reduced commercial-grade tantalum powder, each weighing about 200-800 lbs., were chemically analyzed for suitability as 99.999% Ta feedstock for electron beam melting. Representative samples from each powder lot were analyzed by Glow Discharge Mass Spectrometry (GDMS): powder sublots having combined niobium (Nb), molybdenum (Mo), and tungsten (W) impurity content less than 8 ppm were selected for melting.

The selected Ta powder sublots were then blended in a V-cone blender to produce a homogeneous 4000 pound powder master lot, which was again analyzed by GDMS to confirm purity. Next, the powder was cold isostatically pressed (CIP'ed) into green logs approximately 5.5"-6.5" in diameter, each weighing nominally 300 pounds. The pressed logs were then degassed by heating at 1450°C for 2 hours at a vacuum level of about 10^{-3} - 10^{-5} torr. For this operation, the logs were covered with tantalum sheets to prevent contamination from the furnace elements.

The degassed logs were then side fed into a 1200KW EB furnace and drip melted at a rate of 400 lbs./hr. into a 10" water-cooled copper crucible under a vacuum less than 10^{-3} torr. Once cooled, the resulting first-melt ingot was inverted, hung in the same furnace, and remelted using the same EB melting parameters. The 2nd melt ingot was again inverted and remelted a third time, but into a 12" crucible at a melt rate of 800 lbs./hr.

A sample was taken from the sidewall of the resulting ingot for chemical analysis by Glow Discharge Mass Spectrometry (GDMS). Results confirmed that the Ta ingot was 99.9992% pure.

Example 2

A potassium fluotantalate (K_2TaF_7) was obtained and upon spark source mass spec analysis, the K_2TaF_7 exhibited 5 ppm or less niobium. Levels of Mo and W were also analyzed by spectrographic detection and levels were below 5 ppm for Mo and below 100 ppm for W. In particular, the K_2TaF_7 had levels of Nb of 2 ppm or less, of Mo of less than 1 ppm and of W of less

than or equal to 2 ppm. In each sample, the total recorded amount of Nb, Mo, and W was below 5 ppm. Four lots of 2,200 lbs. each were analyzed.

One of the lots was transferred to KDEL reactor which used a pure nickel vessel and a Hastelloy X agitator. The Hastelloy X agitator contained 9% Mo and 0.6% W. The shaft and paddles of the agitator were then shielded with 1/16" nickel sheet using welding to clad all surfaces exposed to the reaction.

A standard sodium reduction process was used except as noted below. The lot was subjected to the agitator in the presence of pure sodium to form tantalum powder. The tantalum powder was then washed with water and subjected to acid treating and then steam drying and then screening to 100 mesh.

A sample from each batch was then submitted for glow discharge mass spec analysis. The two tables (Tables 1 and 2) below show the starting analysis for the K_2TaF_7 and the final analysis of the tantalum recovered.

Table 1

 K_2TaF_7 Spark Source Mass Spec (SSMS) Analysis

(metal to salt basis)

Sample Number	Nb (ppm)	Mo (ppm)	W (ppm)	TOTAL (ppm)
1	2	<1	≤2	<5
2	1	<1	≤2	<4
3	2	<1	≤2	<5
4	1	<1	≤2	<4

Table 2

Ta Powder Glow Discharge Mass Spec (GDMS) Analysis

Sample Number	Nb (ppm)	Mo (ppm)	W (ppm)	TOTAL (ppm)
5	1.4	0.38	0.27	2.05
6	1.2	0.30	0.50	2.00
7	1.0	0.25	0.29	1.54
8	1.1	0.15	0.28	1.53

As can be seen in the above tables, a high purity tantalum powder suitable for electron beam melting into an ingot can be obtained and purities on the order of 99.999% purity can be obtained by the processing shown in Example 1.

Example 3.

Two distinct process methodologies were used. First, a 99.998% pure tantalum ingot was used which was subjected to three electron beam melts to produce a 12 inch nominal diameter ingot. The ingot was machined clean to about 11½ inch diameter and then heated in air to about 260°C for 4-8 hours. The ingot was then flat forged, cut, and machined into slabs (approximately 4 inch by 10 inch with a length of approximately 28 inch to 32 inch) and then acid cleaned with HF/HNO₃/water solution. The slabs were annealed at 1050, 1150, and 1300°C under vacuum of 5×10^{-4} Torr for 2 hours, then cold rolled into plate stock of 0.500 and 0.250" gauge. This cold rolling was accomplished by taking a 4 inch thick by 10 inch wide by 30 inch long slab and rolling it perpendicular to the ingot axis at 0.200 inch per pass to 31 inches wide. The plate was then rolled parallel to the ingot axis at 0.100 inch per pass to 0.650 inch thick or 0.500 inch thick. Both rollings were done on a 2-High breakdown rolling mill. Each of the plates were rolled by multiples passes of 0.050 inch per pass and then 0.025 inch per pass with final adjustments to meet a finish gauge of 0.500 inch plate or 0.250 inch plate, using a four high finishing rolling mill. The plates were then subjected to a final annealing at temperatures of from 950 - 1150°C.

The alternative process began with a 99.95 % pure Ta which was subjected to three electron beam melts to produce an ingot as described above prior to being forged. The ingot was then round forged using a GFM rotary forge to 4" diameter after multiples passes of about 20% reduction in area per pass. From this intermediate stock, 4 billets (3.75"Ø x 7" long) were machined, and 2 billets (labeled A and B) were annealed at 1050°C while billets C and D remained unannealed. Next, the billets were upset forged to performs of height of 2.5", after which performs A and C were annealed at 1050°C. The performs were then clock rolled to a thickness of about 0.400" to yield discs of a diameter of approximately 14". This was accomplished by taking multiple

5 passes of 0.200 inch per pass to about 0.5250 inch thick. The discs were then rolled to about 0.5
10 inch thick by multiple passes of 0.100 inch per pass. Then, the discs were clocked rolled on a four
high finishing mill in three passes of 0.050 inch, 0.025 inch, and 0.015 inch reductions per pass to
15 yield a disc of about 0.400 inch thick by about 14 inch diameter. A quarter of the disc was cut into
four wedges and final annealed at temperatures of 950-1100°C. Table 4 below summarizes this
processing.

20 Metallographic and texture analysis was conducted on longitudinal sections of the plate
material (measurement face parallel to the final rolling direction) and on radial sections of the
forged and rolled discs (measurement face parallel to the radius of the discs).

10

METALLURGICAL ANALYSIS

25 Grain size and texture were measured along the longitudinal or radial directions of samples
taken from rolled plate and forged and rolled discs, respectively. Grain size was measured using
ASTM procedure E-112. Results from the annealing studies on products produced via the flat and
30 round processes are given in Tables 3 and 4, respectively. Intermediate annealing treatments had no
noticeable influence on the grain size of the finished product. Also, for plate, the final grain sizes
35 of 0.500 and 0.250" thick tantalum were comparable. The only variable found to significantly
effect the grain size of the materials was the final anneal temperature: the higher the final anneal
temperature, the larger the resulting grain size.

40 20 In plate, grain sizes of ASTM 6.5 - 7.0 were measured in samples from product annealed at
1000 and 950°C. However, each of these samples showed evidence of elongated and/or
unrecrystallized regions at or near the surface, and recrystallization values were reported to be 98-
45 99%. For plates annealed at 1050, 1100, and 1150°C, ASTM grain sizes ranged from 5.3 to 3.7,
with all samples being 100% recrystallized.

25 50 For the round-processed discs, all samples were reported to be 100% recrystallized, with
the exception of Disc C annealed at 950°C which was 99% recrystallized. Grain sizes of ASTM 7.1-

5 7.2, 6.1-6.8, and 5.9-5.9 were measured in the disc samples annealed at 950, 1000, and 1050°C, respectively. Annealing at 1100°C produced grain sizes of ASTM 4.0-4.5.

10 For both processes, these findings demonstrate that a fully recrystallized grain size of 50 μm or finer is achievable using either the plate rolling or the billet forging process at a preferred
5 final anneal temperature of from about 950 to about 1050°C. Should the unrecrystallized areas be
15 limited to only the surface regions of the plate, then they can be removed by machining.

Texture Measurement Technique: A limited number of samples (chosen based on
20 metallurgical results) were used for texture analysis. Mounted and polished samples, previously
10 prepared for metallurgical analysis, were employed as texture samples after being given a heavy
acid etch prior to texture measurement. Orientation Imaging Microscopy (OIM) was chosen as the
25 method of texture analysis because of its unique ability to determine the orientation of individual
grains within a polycrystalline sample. Established techniques such as X-ray or neutron diffraction
would have been unable to resolve any localized texture variations within the thickness of the
tantalum materials.

30 15 For the analysis, each texture sample was incrementally scanned by an electron beam
(within an SEM) across its entire thickness; the backscatter Kikuchi patterns generated for each
35 measurement point was then indexed using a computer to determine the crystal orientation. From
each sample, a raw-data file containing the orientations for each data point within the measurement
grid array was created. These files served as the input data for subsequently producing grain
40 20 orientation maps and calculating pole figures and orientation distribution functions (ODFs).

By convention, texture orientations are described in reference to the sample-normal
45 coordinate system. That is, pole figures are "standardized" such that the origin is normal to the
plate surface, and the reference direction is the rolling (or radial) direction; likewise, ODFs are
always defined with respect to the sample-normal coordinate system. Terminology such as "a (111)
25 texture" means that the (111) atomic planes are preferentially oriented to be parallel (and the (111)
50 pole oriented to be normal) with the surface of the plate. In the analyses, the crystal orientations

5 were measured with respect to the sample longitudinal direction. Therefore, it was necessary to
transpose the orientation data from the longitudinal to sample-normal coordinate system as part of
10 the subsequent texture analysis. These tasks were conducted through use of computer algorithms.

Grain Orientation Maps: Derived from principles of presenting texture information in the
5 form of inverse pole figures, orientation maps are images of the microstructure within the sample
15 where each individual grain is "color-coded " based on its crystallographic orientation relative to
the normal direction of the plate of disc from which it was taken. To produce these images, the
crystal axes for each grain (determined along the longitudinal direction of the texture sample by
20 OIM) were tilted 90° about the transverse direction so to align the crystal axes to the normal
10 direction of the sample. Orientation maps serve to reveal the presence of texture bands or gradients
through the thickness on the product; in tantalum, orientation maps have shown that large,
25 elongated grains identified by optical microscopy can be composed of several small grains with
low-angle grain boundaries.

Analysis of the Texture Results: OIM scans were taken along the thickness of each sample
30 provided; for the 0.500" plate samples, separate measurements were made for the top and the
15 bottom portions of the plate and reported separately.

35 The orientation maps were visually examined to qualitatively characterize the texture
uniformity through the sample thickness. To attain a quantifiable description of the texture
gradients and texture bands in the example materials, the measured EBSD data was partitioned into
40 20 subsets, with each representing a 5% increment of depth through the thickness of the sample.
For each incremental data set, an ODF was first calculated, then (100) and (111) centroid intensities
determined numerically using techniques reported elsewhere. The equipment and procedures
45 described in S. Matthies et al., Materials Science Forum, Vol. 157-162 (1994), pp. 1647-1652 and
S. Matthies et al., Materials Science Forum, Vol. 157-162 (1994), pp. 1641-1646 were applied, and
25 these publications are incorporated in their entirety herein by reference. The texture gradients were
50 then described graphically by plotting the (100) and (111) intensities, as well as the log ratio of the
55

5 (100):(111), as a function depth of the sample. These results are set forth in Figures I (A and B) through Figures II (A and B).

10 The heavy-gauge tantalum plate exhibited the most uniform through-thickness texture; the only sample containing texture bands was that processed with a slab anneal of 1300°C and a final
5 anneal of 1000°C. In addition, the 0.500" plate materials also had a relative weak (most random) texture base on pole figure and ODF analysis. Compared to the heavy plate, the 0.250' sheets
15 contained a slight to moderate texture gradient and some evidence of texture banding. Also, the thin-gauge plates showed a more defined (111) texture in the ODFs and an increased prominence of
20 (100).

10 The greatest variability in terms of texture uniformity and banding was found in the forged and rolled discs. Unlike the metallurgical properties, the texture of forged and rolled discs was
25 effected by the use of intermediate annealing. For discs A, B, and C, each of which were processed with one or two intermediate annealing steps, the texture gradients ranged from negligible to strong
30 (depending to processing parameters) with slight - if any - banding. However, for disc D, which
15 was worked from ingot to final discs without intermediate annealing, the resultant product contained less desirable strong texture gradients and sharp texture bands. Similarly, disc C, which
35 was also forged from unannealed billet but then annealed prior to cold rolling, also showed a strong texture gradient and banding in the sample final annealed at 950°C. For disc C, increasing the final
anneal temperature to 1100°C acted to diminish the gradient, eliminated the bands, but
40 20 strengthening the intensity of (100) texture component. These effects from increasing final annealing temperatures were also evident, but to a lesser degree, in both the other disc materials and the heavy gauge plate.

45 From the microstructural and textural observations, the following conclusions could be made regarding the optimum processing for fabricating tantalum sputtering targets:

- For flat products, slab anneal temperatures preferably do not exceed 1150°C (1050°C is more preferred) and the final anneal temperature is preferably kept at 950-1000°C, more preferably 1000°C. The resulting product is characterized as having a recrystallized average grain size of less 50 μm , and a (100) incremental intensity of less than 15 random and a log ratio of (111):(100) of less than -4.0.
- For round processing, billets preferably are annealed prior to forging and rolling into disc without use of an intermediate anneal at perform level. Final anneal temperature is preferably 950-1100°C., and more preferably is 1050°C. The resulting product is characterized as having a recrystallized average grain size below 50 μm , and a (100) incremental intensity of less than 15 random and a log ratio of (111):(100) of less than -4.0.

Table 3 (cont)

Slab Anneal Temperature (°C)	1300			
Gauge of Plate Produced from Slab	.250"		.500"	
Plate Anneal Temperature (°C)	ASTM Grain Size	% Recry.	ASTM Grain Size	% Recry.
950	7.0	98	6.7	98
1000	6.5	99	6.5	98
1050	4.5	100	5.3	100
1050	5.0	100	4.5	100
1100	4.5	100	4.0	100
1150	4.0	100	3.7	100

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Table 4

BILLET A	BILLET B	BILLET C	BILLET D	PC.WEIGHT	
<u>Anneal</u> <u>1050 C</u>	<u>Anneal</u> <u>1050 C</u>	<u>Unannealed</u>	<u>Unannealed</u>	46.4 lbs	7" Long
Upset Forge 2.5" Thick	Upset Forge 2.5" Thick	Upset Forge 2.5" Thick	Upset Forge 2.5" Thick		6.25" Diameter
Anneal 1050C		Anneal 1050C			
Machine Clean	Machine Clean	Machine Clean	Machine Clean	42 lbs	6" Diameter
X-Roll to Gauge 0.400"	X-Roll to Gauge 0.400"	X-Roll to Gauge 0.400"	X-Roll to Gauge 0.400"		15" Diameter
Saw Cut Quarters	Saw Cut Quarters	Saw Cut Quarters	Saw Cut Quarters	10.5 lbs/qr.	
Anneal Study	Anneal Study	Anneal Study	Anneal Study		
ANNEAL TEMP(°C)	ASTM GRAIN SIZE (REX)				
950	7.1 (100%)	7.2 (100%)	7.1 (99%)	7.2 (100%)	
1000	6.1 (100%)	6.5 (100%)	5.9 (100%)	6.8 (100%)	
1050	5.8 (100%)	5.9 (100%)	5.9 (100%)	5.9 (100%)	
1100	4.5 (100%)	4.5 (100%)	4.5 (100%)	4.0 (100%)	

REX = % Recrystallization

0.500" PLATE 139

Slab Anneal: 1050 Plate Anneal: 950

Grain Size: 6.7

Increment: 0.025"

Increment	(111)	(100)	ln(ratio)
1	1.257	1.908	-0.42
2	0.703	1.456	-0.73
3	1.127	1.11	0.02
4	1.554	1.543	0.01
5	0.279	1.146	-1.41
6	1.159	1.774	-0.43
7	1.481	1.335	0.10
8	3.27	1.086	1.10
9	0.996	1.072	-0.07
10	2.337	1.634	0.36
11	4.81	1.011	1.56
12	3.321	2.885	0.14
13	2.294	2.73	-0.17
14	1.477	1.329	0.11
15	0.607	1.229	-0.71
16	1.02	0.281	1.29
17	1.536	0.634	0.88
18	1.771	4.277	-0.88
19	1.057	1.921	-0.60
20	0.097	1.051	-2.38

0.500" PLATE 142

Slab Anneal: 1050 Plate Anneal: 1000

Grain Size: 6.5

Increment: 0.025"

Increment	(111)	(100)	ln(ratio)
1	3.502	3.495	0.00
2	0.848	2.988	-1.28
3	0.412	3.998	-2.27
4	0.304	0.878	-0.80
5	0.52	0.717	-0.32
6	1.167	1.401	-0.18
7	1.493	1.691	-0.12
8	2.071	1.445	0.38
9	2.039	1.77	0.14
10	2.19	1.643	0.29
11	1.541	0.327	1.55
12	6.722	0.091	4.30
13	4.228	0.131	3.47
14	1.904	1.455	0.27
15	1.514	2.136	-0.34
16	1.366	1.28	0.08
17	1.388	0.904	0.43
18	0.709	1.504	-0.75
19	0.615	0.395	0.44
20	1.027	0.499	0.72

0.500" PLATE 140

Slab Anneal: 1150 Plate Anneal: 1000

Grain Size: 6.5

Increment: 0.025"

Increment	(111)	(100)	ln(ratio)
1	1.786	1.286	0.33
2	1.745	0.433	1.39
3	1.948	0.782	0.91
4	3.232	2.3	0.34
5	2.892	3.517	-0.20
6	1.061	3.701	-1.25
7	3.501	0.522	1.90
8	1.026	1.944	-0.64
9	4.783	0.608	2.06
10	2.402	0.535	1.50
11	3.097	2.547	0.20
12	0.859	2.571	-1.10
13	2.585	0.897	1.06
14	0.872	2.955	-1.22
15	1.439	1.28	0.12
16	1.857	2.131	-0.25
17	1.395	1.765	-0.24
18	2.506	1.105	0.82
19	1.541	1.381	0.11
20	0.593	1.696	-1.05

0.500" PLATE 141

Slab Anneal: 1300 Plate Anneal: 1000

Grain Size: 6.5

Increment: 0.025"

Increment	(111)	(100)	ln(ratio)
1	1.577	3.039	-0.66
2	1.125	1.032	0.09
3	1.007	1.824	-0.59
4	2.001	0.698	1.05
5	2.091	2.748	-0.27
6	4.892	1.906	0.94
7	0.886	4.336	-1.59
8	6.052	0.882	1.93
9	3.392	0.317	2.37
10	2.177	1.376	0.46
11	3.431	2.973	0.14
12	3.628	1.589	0.83
13	3.458	0.637	1.69
14	2.095	1.368	0.43
15	1.869	1.023	0.60
16	1.371	2.226	-0.48
17	2.032	1.143	0.58
18	1.949	1.754	0.11
19	2.175	3.521	-0.48
20	5.092	2.802	0.60

0.250" PLATE 125D

Slab Anneal: 1050 Plate Anneal: 1000

Grain Size: 6.5

Increment: 0.0125"

Increment	(111)	(100)	ln(ratio)
1	2.241	4.137	-0.61
2	1.411	4.259	-1.10
3	0.823	3.941	-1.57
4	0.82	7.79	-2.25
5	1.734	4.658	-0.99
6	2.812	7.527	-0.98
7	5.245	4.266	0.21
8	6.196	2.283	1.00
9	8.892	1.248	1.96
10	8.531	1.082	2.06
11	5.261	1.857	1.04
12	1.439	1.097	0.27
13	2.445	2.493	-0.02
14	2.057	5.962	-1.06
15	1.173	2.213	-0.63
16	1.767	2.609	-0.39
17	0.55	4.066	-2.00
18	2.921	4.855	-0.51
19	4.431	3.684	0.18
20	6.313	1.898	1.20

0.250" PLATE 125B

Slab Anneal: 1150 Plate Anneal: 1000

Grain Size: 6.5

Increment: 0.0125"

Increment	(111)	(100)	ln(ratio)
1	4.159	2.577	0.48
2	6.06	0.27	3.11
3	4.407	0.964	1.52
4	2.336	1.175	0.69
5	2.023	2.155	-0.06
6	3.733	2.091	0.58
7	4.117	2.131	0.66
8	4.718	2.721	0.55
9	5.367	2.604	0.72
10	2.876	5.519	-0.65
11	4.952	2.886	0.54
12	4.12	3.362	0.20
13	2.752	1.715	0.47
14	0.949	4.93	-1.65
15	1.108	4.827	-1.47
16	1	3.157	-1.15
17	2.357	6.294	-0.98
18	0.846	10.654	-2.53
19	1.628	5.369	-1.19
20	0.866	4.458	-1.64

0.250" PLATE 125C
 Slab Anneal: 1300 Plate Anneal: 1000
 Grain Size: 6.5
 Increment: 0.0125"

Increment	(111)	(100)	ln(ratio)
1	2.154	1.516	0.35
2	1.174	1.282	-0.09
3	0.79	5.848	-2.00
4	0.981	2.736	-1.03
5	1.938	3.55	-0.61
6	2.302	3.179	-0.32
7	5.221	1.661	1.15
8	3.636	2.6	0.34
9	2.982	1.083	1.01
10	6.161	0.322	2.95
11	7.636	0.623	2.51
12	7.336	0.46	2.77
13	4.415	6.945	-0.45
14	2.37	1.953	0.19
15	2.516	3.636	-0.37
16	1.99	1.976	0.01
17	2.696	0.769	1.25
18	3.155	5.257	-0.51
19	4.558	0.879	1.65
20	1.788	0.595	1.10

0.400" FORGING 950A
 Billet Anneal: 1050 Preform Anneal: 1050
 Finish Anneal: 950 Grain Size: 7.1
 Increment: 0.020"

Increment	(111)	(100)	ln(ratio)
1	2.127	6.911	-1.18
2	4.289	4.447	-0.04
3	3.421	4.819	-0.34
4	3.065	4.67	-0.42
5	3.879	4.872	-0.19
6	2.33	5.309	-0.82
7	8.206	1.239	1.89
8	9.086	0.57	2.77
9	9.615	0.425	3.12
10	10.558	1.57	1.91
11	12.83	0.883	2.68
12	9.168	2.094	1.48
13	8.395	2.002	1.43
14	11.219	3.961	1.04
15	2.512	3.816	-0.42
16	5.044	4.613	0.09
17	3.898	6.144	-0.46
18	2.297	6.159	-0.99
19	5.796	6.809	-0.16
20	2.799	6.72	-0.88

0.400" FORGING 950B

Billet Anneal: 1050 Preform Anneal: N/A

Finish Anneal: 950 Grain Size:

Increment: 0.020"

Increment	(111)	(100)	ln(ratio)
1	8.364	6.785	0.21
2	8.193	6.839	0.18
3	6.576	6.901	-0.05
4	4.947	6.953	-0.34
5	3.246	8.833	-1.00
6	5.807	7.248	-0.22
7	7.812	5.491	0.35
8	9.74	5.358	0.60
9	11.63	3.748	1.13
10	11.544	2.258	1.63
11	11.965	3.086	1.36
12	9.512	6.106	0.44
13	8.558	9.762	-0.13
14	10.727	5.84	0.61
15	6.759	8.025	-0.17
16	6.212	9.528	-0.43
17	3.868	8.796	-0.82
18	6.368	8.333	-0.27
19	6.336	7.45	-0.16
20	4.463	6.201	-0.33

0.400" FORGING 950C

Billet Anneal: N/A Preform Anneal: 1050

Finish Anneal: 950 Grain Size:

Increment: 0.020"

Increment	(111)	(100)	ln(ratio)
1	3.589	9.599	-0.98
2	3.214	8.069	-0.64
3	2.869	6.976	-0.89
4	3.991	8.405	-0.74
5	4.737	3.069	0.43
6	7.163	4.567	0.45
7	7.97	2.348	1.22
8	15.184	0.506	3.40
9	18.894	0.058	5.79
10	16.416	0.084	5.28
11	12.528	0.215	4.07
12	13.644	1.074	2.54
13	9.229	1.141	2.09
14	4.285	6.858	-0.47
15	2.067	4.102	-0.69
16	3.938	4.881	-0.21
17	3.391	10.311	-1.11
18	5.302	6.265	-0.17
19	5.755	6.608	-0.14
20	4.701	8.166	-0.55

0.400" FORGING 950D

Billet Anneal: N/A Preform Anneal: N/A
Finish Anneal: 950 Grain Size:
Increment: 0.020"

Increment	(111)	(100)	ln(ratio)
1	1.836	9.65	-1.66
2	4.837	7.584	-0.45
3	5.785	5.354	0.08
4	1.468	10.297	-1.95
5	0.781	17.101	-3.09
6	8.097	9.559	-0.17
7	18.984	1.486	2.55
8	25.471	0.168	5.03
9	31.554	0.053	6.39
10	29.911	0.075	5.99
11	25.476	0.055	6.14
12	21.407	1.494	2.66
13	6.505	2.777	0.85
14	0.065	1.665	-3.24
15	0.052	4.2	-4.39
16	0.528	9.288	-2.87
17	1.122	8.954	-2.08
18	2.67	8.715	-1.18
19	5.137	8.222	-0.47
20	1.453	10.944	-2.02

5 Other embodiments of the present invention will be apparent to those skilled in the art from
consideration of the present specification and practice of the present invention disclosed herein. It is
10 intended that the present specification and examples be considered as exemplary only with a true
scope and spirit of the invention being indicated by the following claims.

Claims

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WHAT IS CLAIMED IS:

1. Tantalum metal having a purity of at least about 99.995%, and an average grain size of about 150 microns or less.
2. The tantalum metal of claim 1, wherein said metal is fully recrystallized.
3. The tantalum metal of claim 1, wherein said metal is at least partially recrystallized.
4. The tantalum metal of claim 1, wherein about 98% or more of said metal is recrystallized.
5. The tantalum metal of claim 1, wherein about 80% or more of said metal is recrystallized.
6. The tantalum metal of claim 1, wherein said metal has a) a texture in which a (100) pole figure has a center peak intensity less than about 15 random or b) a log ratio of (111):(100) center peak intensities of greater than about -4.0, or c) both.
7. The tantalum metal of claim 6, wherein said center peak intensity is from about 0 random to about 15 random.
8. The tantalum metal of claim 6, wherein said center peak intensity is from about 0 random to about 10 random.
9. The tantalum metal of claim 6, wherein said log ratio is from about -4.0 to about 15.
10. The tantalum metal of claim 6, wherein said log ratio is from about -1.5 to about 7.0.
11. The tantalum metal of claim 6, wherein said center peak intensity is from about 0 random to about 15 random, and said log ratio is from about -4.0 to about 15.
12. The tantalum metal of claim 1 having a purity of from 99.995% to about 99.999%.
13. A metal alloy comprising the tantalum metal of claim 1.
14. A metal alloy comprising the tantalum metal of claim 6.
15. A metal alloy comprising the tantalum metal of claim 3.
16. A sputtering target comprising the tantalum metal of claim 1.
17. A sputtering target comprising the tantalum metal of claim 6.

- 5 18. A sputtering target comprising the tantalum metal of claim 3.
19. A capacitor can comprising the tantalum metal of claim 1.
- 10 20. A capacitor can comprising the tantalum metal of claim 6.
21. A capacitor can comprising the tantalum metal of claim 3.
- 5 22. A resistive film layer comprising the tantalum metal of claim 1.
- 15 23. A resistive film layer comprising the tantalum metal of claim 6.
24. A resistive film layer comprising the tantalum metal of claim 3.
25. An article comprising at least as a component the tantalum metal of claim 1.
- 20 26. An article comprising at least as a component the tantalum metal of claim 6.
- 10 27. An article comprising at least as a component the tantalum metal of claim 3.
- 25 28. Tantalum metal having a) an average grain size of about 50 microns or less, or b) a texture in which a (100) pole figure has a center peak intensity equal to or less than about 15 random or c) a log ratio of (111):(100) center peak intensities of greater than about -4.0, or combinations thereof.
- 30 29. The tantalum metal of claim 28 having an average grain size of from about 25 to about 50
- 15 microns.
30. The tantalum metal of claim 28 having a ratio of (111):(100) center peak intensities of greater than about -4.0.
- 35 31. The tantalum metal of claim 28, having both a) and b).
32. The tantalum metal of claim 28, wherein said metal has purity of at least 99.995% tantalum.
- 40 20 33. The tantalum metal of claim 28, wherein said metal has a purity of 99.999% tantalum.
34. The tantalum metal of claim 28, wherein said metal is fully recrystallized.
35. The tantalum metal of claim 32, wherein said metal is fully recrystallized.
- 45 36. The tantalum metal of claim 33, wherein said metal is fully recrystallized.
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5 37. The tantalum metal of claim 28, wherein about 80% or more of said metal is fully recrystallized.

10 38. The tantalum metal of claim 28, wherein said center peak intensity is from about 0 random to about 15 random.

5 39. The tantalum metal of claim 28, wherein said log ratio is from about -4.0 to about 15.

15 40. An article comprising the tantalum metal of claim 28.

41. An article comprising the tantalum metal of claim 33.

42. A sputtering target comprising the tantalum metal of claim 28.

20 43. A sputtering target comprising the tantalum metal of claim 33.

10 44. A process for making the tantalum metal of claim 1, comprising reacting a salt containing tantalum with at least one agent capable of reducing the salt to tantalum and a second salt in a reaction container having an agitator, wherein the reaction container or a liner in the reaction container and the agitator or a liner on the agitator are made from a metal material having the same or higher vapor pressure of tantalum at the melting point of the
30 15 tantalum.

45. The process of claim 44, wherein the salt containing tantalum comprises a potassium-fluoride tantalum and the agent comprises sodium.
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46. The process of claim 45, wherein the second salt comprises sodium fluoride and/or sodium chloride.

40 20 47. The process of claim 44, wherein prior to reacting said salt containing tantalum, said process comprising forming an acid solution comprising tantalum and impurities and conducting a density separation of the acid solution containing tantalum from the acid solution containing the impurities; and crystallizing the acid solution containing the
45 tantalum to form the salt containing tantalum.

5 48. The process of claim 47, wherein the tantalum and impurities are crushed ore comprising tantalum and impurities.

10 49. The process of claim 47, wherein the acid solution comprising tantalum and impurities are formed by combining acid solution with crushed ore comprising
5 tantalum.

15 50. The process of claim 44, wherein the reaction occurs at about 800°C to about 1100°C while stirring.

20 51. The process of claim 44, wherein the reaction container or liner and the agitator or liner on the agitator are metal-based, wherein said metal is nickel, chromium, iron, manganese,
10 titanium, zirconium, hafnium, vanadium, technetium, ruthenium, cobalt, rhodium, palladium, platinum, or any combination thereof.

25 52. The process of claim 51, wherein the metal is nickel or a nickel-based alloy.

53. The process of claim 51, wherein the metal is chromium or a chromium-based alloy.

30 54. The process of claim 51, wherein the metal is iron or an iron-based alloy.

55 55. The process of claim 44, further comprising recovering tantalum by dissolving the second salt in an aqueous solution.

35 56. The process of claim 55, further comprising melting said recovered tantalum in a sufficient vacuum to remove substantially any existing impurities in said recovered
40 20 tantalum and obtain high purity tantalum.

57. The process of claim 56, wherein the vacuum is 10^{-4} torr or more.

45 58. The process of claim 56, wherein the pressure above the melted recovered tantalum is lower than the vapor pressures of substantially all of the impurities.

5 59. The process of claim 56, wherein the impurities are removed by vaporization of the impurities.

10 60. The process of claim 56, wherein said melting is accomplished by electron beam melting.

15 61. The process of claim 56, wherein said melting is accomplished by vacuum arc remelt processing.

62. The process of claim 56, wherein the high purity tantalum is allowed to form a solid and subjected to a rolling process, a forging process, or both.

20 63. The tantalum metal of claim 1, wherein the tantalum metal has a substantially fine and uniform microstructure.

25 64. The tantalum metal of claim 1, wherein the tantalum metal has an average grain size of from about 25 to about 150 microns.

30 65. The tantalum metal of claim 64, wherein the tantalum metal has an average grain size of from about 25 to about 100 microns.

15 30 66. The tantalum metal of claim 65, wherein the tantalum metal has an average grain size of from about 25 to about 75 microns.

35 67. A process of making a sputtering target from tantalum metal having a purity of at least 99.995%, comprising:

40 20 a) mechanically or chemically clean surfaces of the tantalum metal, wherein the tantalum metal has a sufficient starting cross-sectional area to permit steps b) through g);

45 b) flat forging the tantalum metal into at least one rolling slab, wherein the at least one rolling slab has sufficient deformation to achieve substantially uniform recrystallization after annealing in step d);

c) mechanically or chemically clean surfaces of the at least one rolling slab;

5 d) annealing the at least one rolling slab at a sufficient temperature and for a sufficient time to achieve at least partial recrystallization of the at least one rolling slab;

10 e) cold or warm rolling the at least one rolling slab in both the perpendicular and parallel directions to the axis of the starting tantalum metal to form at least one plate;

5 f) flattening the at least one plate; and

15 g) annealing the at least one plate to have an average grain size equal to or less than about 150 microns and a texture substantially void of (100) textural bands;

68. The process of claim 67, wherein the tantalum metal has a purity of at least 99.999%.

20 69. The process of claim 67, wherein the flat forging occurs after the tantalum metal is placed in air for at least about 4 hours and from temperatures ranging from ambient to about 1200°C.

25 70. The process of claim 67, wherein the cold rolling is transverse rolling at ambient temperatures and the warm rolling is at temperatures of less than about 370°C.

30 71. The process of claim 67, wherein the annealing of the plate is vacuum annealing at a temperature and for a time sufficient to achieve recrystallization of the tantalum metal.

35 72. A process of making a sputtering target from tantalum metal having a purity of at least 99.995%, comprising:

a) mechanically or chemically clean surfaces of the tantalum metal, wherein the tantalum

40 20 metal has a sufficient starting cross-sectional area to permit steps b) through i);

b) round forging the tantalum metal into at least one rod, wherein the at least one rod has sufficient deformation to achieve substantially uniform recrystallization after annealing in step

45 d) or step f);

c) cutting the rod into billets and mechanically or chemically clean the surfaces of the billets;

5 d) optionally annealing the billets to achieve at least partial recrystallization;

e) axially forging billets into performs;

10 f) optionally annealing the performs to achieve at least partial recrystallization;

g) cold rolling the performs into at least one plate; and

15 h) optionally mechanically or chemically clean the surfaces of the at least one plate; and

i) annealing the at least one plate to have an average grain size equal to or less than about
150 microns and a texture substantially void of (100) textural bands, wherein annealing occurs
at least in step d) or f) or both.

20 73. The process of claim 72, wherein the tantalum metal has a purity of at least

10 99.999%.

25 74. The process of claim 72, wherein the round forging occurs after subjecting the
tantalum metal to temperatures of about 370°C or lower.

75. The process of claim 72 wherein prior to forging the billets, the billets are
annealed.

30 15 76. The process of claim 72, wherein prior to cold rolling of the performs, the
performs are annealed.

35 77. The process of claim 72, wherein the annealing of the performs is vacuum
annealing at a sufficient temperature and for a time to achieve recrystallization.

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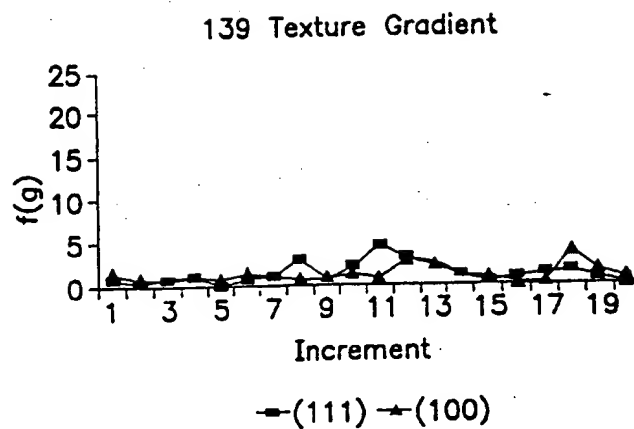


FIG. 1A

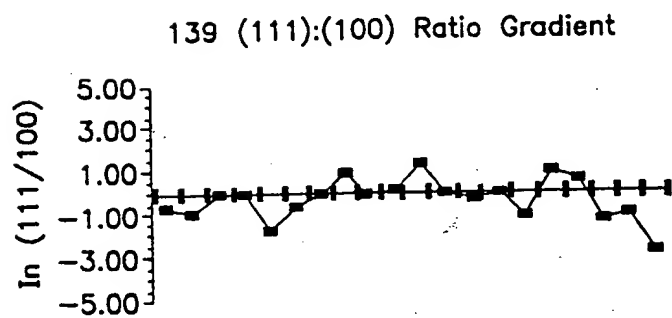


FIG. 1B

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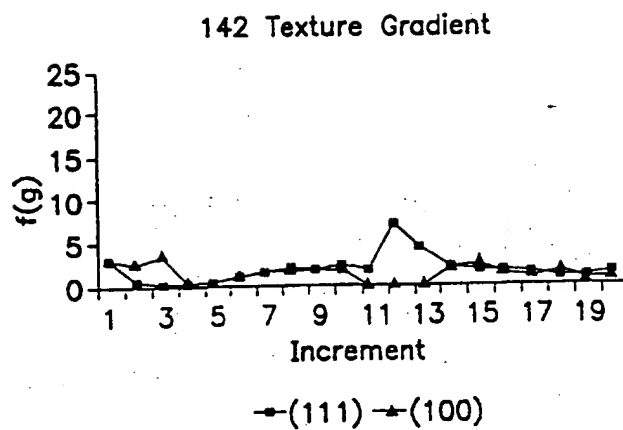


FIG. 2A

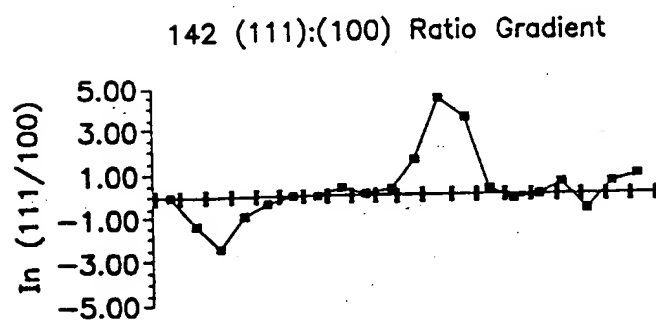


FIG. 2B

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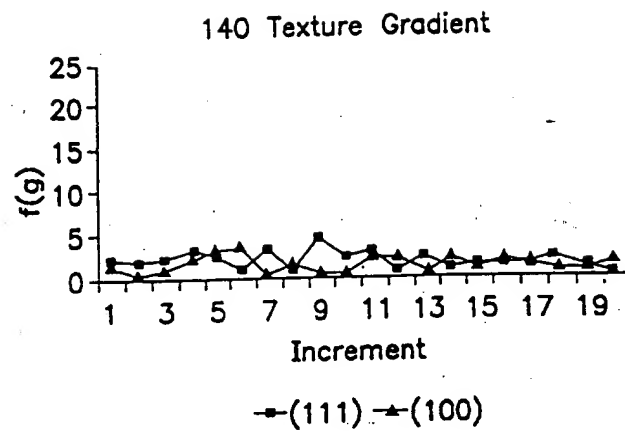


FIG. 3A

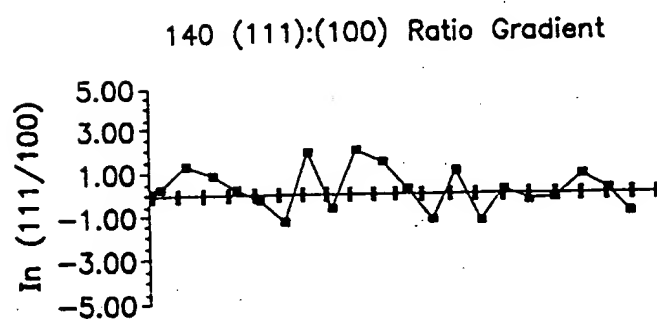


FIG. 3B

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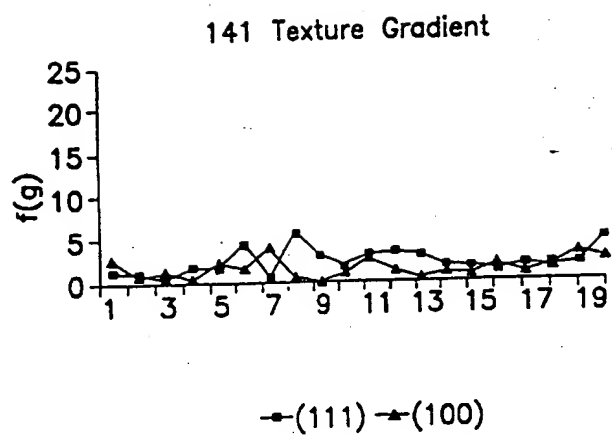


FIG. 4A

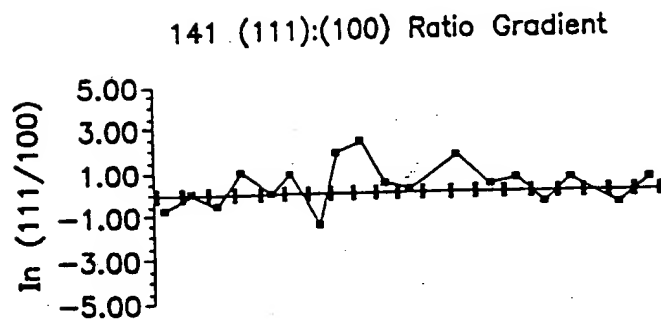


FIG. 4B

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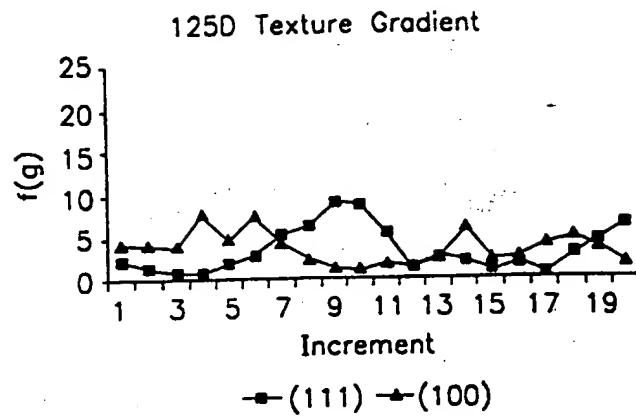


FIG. 5A

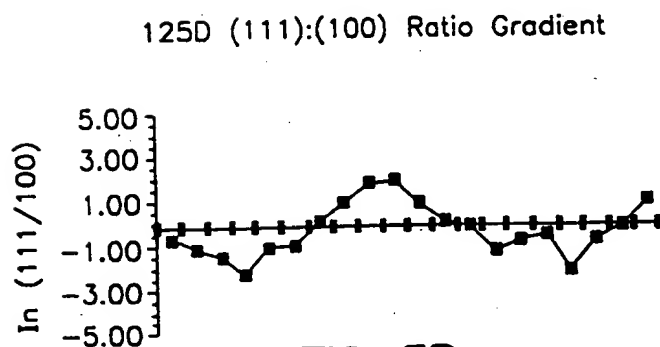


FIG. 5B

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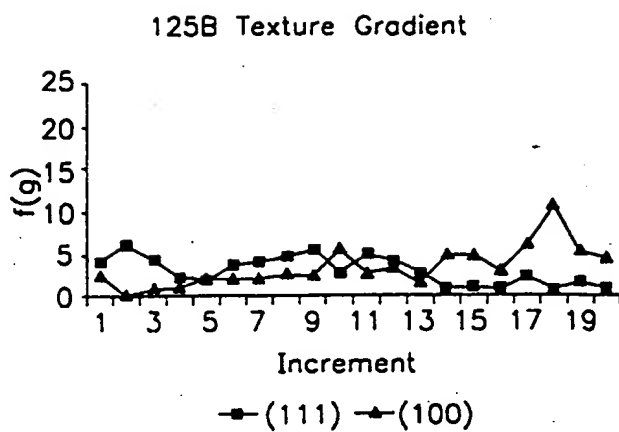


FIG. 6A

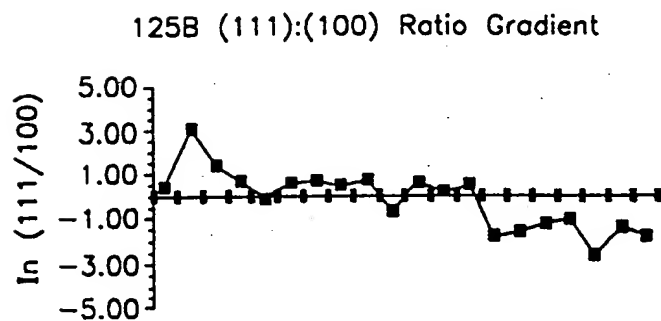


FIG. 6B

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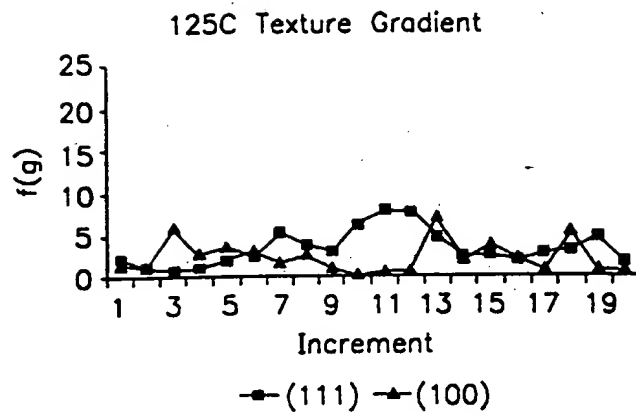


FIG. 7A

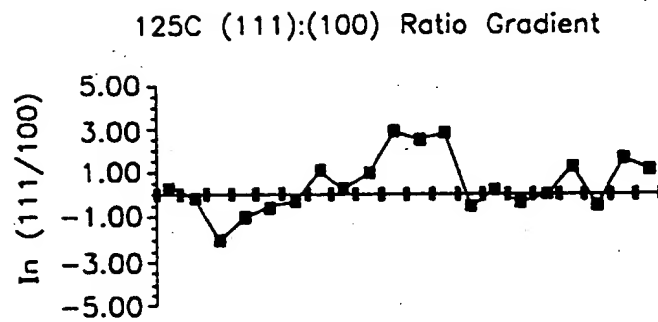


FIG. 7B

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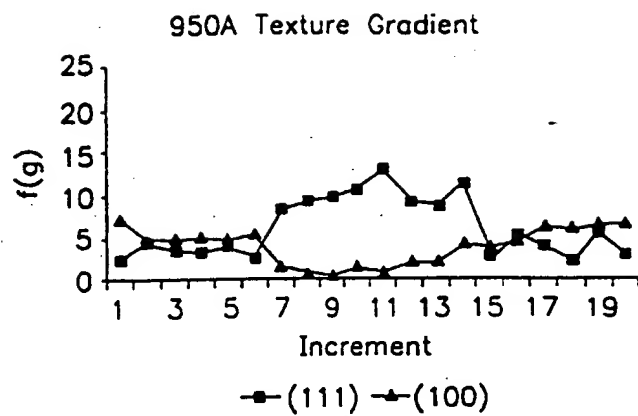


FIG. 8A

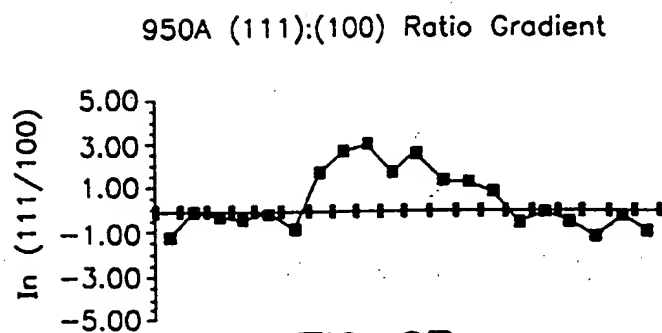


FIG. 8B

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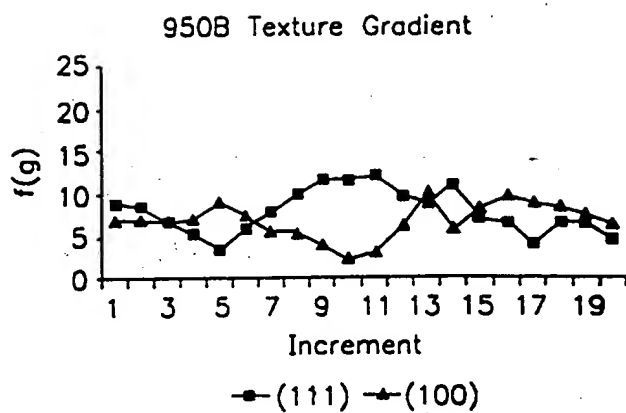


FIG. 9A

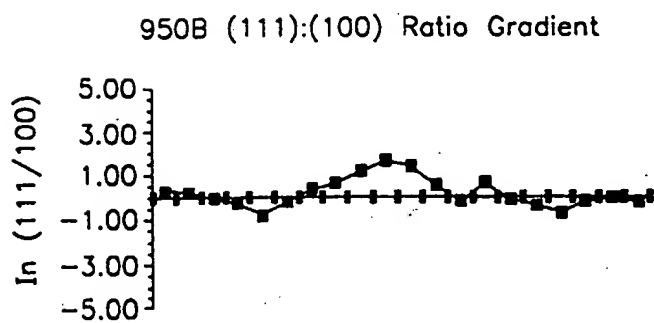


FIG. 9B

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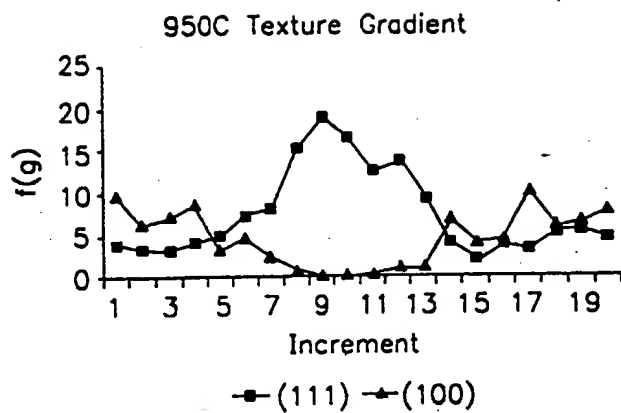


FIG. 10A

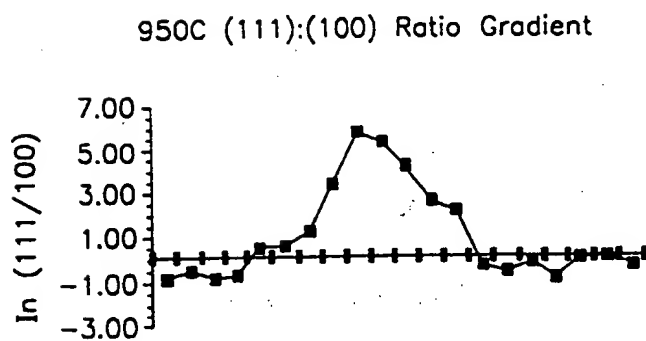


FIG. 10B

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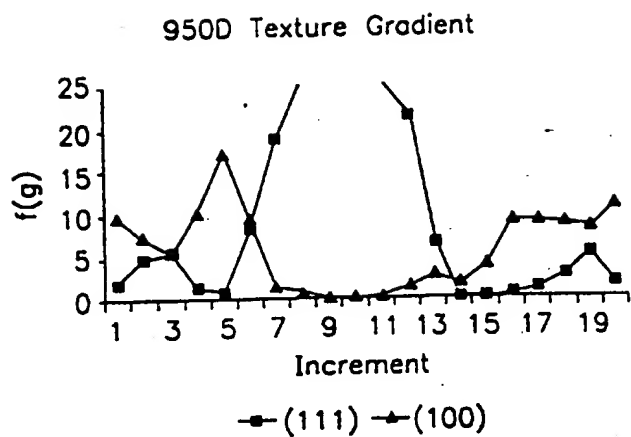


FIG. IIA

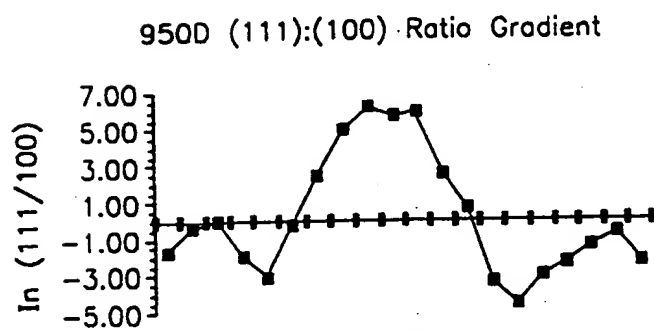


FIG. IIB

International	Location No
PCT/US	99/27832

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INTERNATIONAL SEARCH REPORT

International Application No.
PCT/US 99/27832

C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT		
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X	EP 0 285 741 A (HERAEUS GMBH W C) 12 October 1988 (1988-10-12)	28,29, 34,37,40
Y	page 3, line 42 - line 44; claims 1,2,6	1-5,12, 13,15, 16,18, 19,21, 22,24, 25,27, 32-37, 40-69,71
Y	PATENT ABSTRACTS OF JAPAN vol. 016, no. 495 (P-1436), 14 October 1992 (1992-10-14) & JP 04 178940 A (MITSUBISHI KASEI CORP), 25 June 1992 (1992-06-25) abstract	1,12,32, 33,67,68
Y	PATENT ABSTRACTS OF JAPAN vol. 015, no. 461 (C-0887), 22 November 1991 (1991-11-22) & JP 03 197640 A (TOSHIBA CORP), 29 August 1991 (1991-08-29) abstract	1,12,22, 24,32, 33, 56-60, 67,68
Y	KOCK W ET AL: "TANTALUM-PROCESSING, PROPERTIES AND APPLICATIONS" JOM,US,MINERALS, METALS AND MATERIALS SOCIETY, WARRENDALE, vol. 41, no. 10, 1 October 1989 (1989-10-01), pages 33-39, XP000083911 ISSN: 1047-4838 page 34; figure 3; tables IV,V page 36 -page 38	1-5,12, 13,19, 21,25, 27, 32-37, 40-68
Y	US 5 687 600 A (WILLETT WILLIAM BRYCE ET AL) 18 November 1997 (1997-11-18) cited in the application abstract; figures 1,2	16,18
Y	US 4 141 719 A (HAKKO JAMES B) 27 February 1979 (1979-02-27) column 3, line 14 - line 36; examples 1,7	44-46,61
Y	DATABASE WPI Section Ch, Week 199002 Derwent Publications Ltd., London, GB; Class L03, AN 1990-011129 XP002134104 & JP 01 290766 A (NIPPON MINING CO), 22 November 1989 (1989-11-22) abstract	13,15, 16,18, 56-60
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International Application No.
PCT/US 99/27832

C. (Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT		
Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
E	<p>WO 99 66100 A (JOHNSON MATTHEY ELECT INC) 23 December 1999 (1999-12-23) page 1, line 6-10; claims 1-4 page 3, line 11 -page 8, line 32; figures 1-5</p>	1-43

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Information on patent family members

International Application No
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